

AMENDMENT TO THE ABSTRACT

~~The present invention describes an improved method and apparatus for, among other things, a periodic deposit of a chemical fluid on a regenerate contact surface for the continuous removal of at least one constituent, preferably an odor causing agent, from a gas.~~

In one embodiment the An apparatus for removal of odor from a gas preferably includes an adsorber for the continual removal of an odor-causing agent from a gas is described herein. The apparatus preferably includes an adsorber preferably includes having a sump, a media bed, an exhaust chamber; a chemical fluid entering the exhaust chamber; a regenerate contact surface formed by a periodic deposit of the chemical fluid from the exhaust chamber on the media bed; and a control means for controlling the periodic deposit of the chemical fluid. The sump preferably includes a gas inlet for receiving the gas, and the absorber is configured to allow the gas to flow from the gas inlet to the regenerate contact surface so that at least some of the odor-causing agent is retained by the chemical fluid upon contact of the odor-causing agent with the chemical fluid thereby reducing the amount of odor causing agent in the gas flowing out the exhaust chamber.